

Recipe for MaN-1410 resist

Application

Substrate preparation: it is preferable to process the silicon substrate by evaporation of HMDS at 150°C for 45 sec, using the Delta RC80.

Tone	Negative
Reference	Micro Resist Technology
Spin coat	1.0 μm @3000 RPM
Pre bake	90 sec @100°C on hotplate
Sensitivity	130.5 mJ/cm ²
Exposure time	Approx. ~15 sec @ 8.7 mW/cm ²
Development	1 min in Ma-D 533/s
Stopping of development	30 sec in H ₂ O

Results

Spin curve

